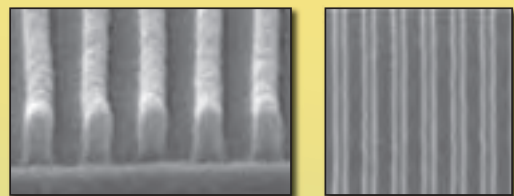


# Compatibility

## Topcoat for ArF Immersion

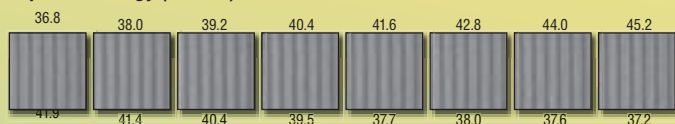
- Good compatibility with commercially-available resists
- Low microbridge defect count and overall defectivity
- Reduced resist contact angle after topcoat removal
- $RCA \geq 72^\circ$
- Excellent process window

### EPIC™ 2096 Photoresist with OC™2000 Series Topcoat



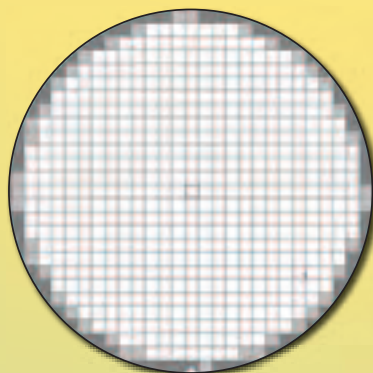
42 nm 1:1 Lines/Spaces with 324Å Topcoat

#### Exposure Energy (mJ/cm²)



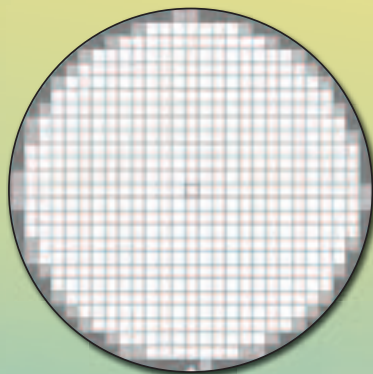
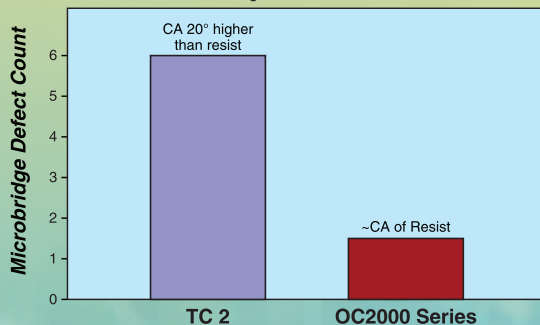
CD (nanometers)

### Low Defectivity of Unexposed Bulk and Exposed Areas



Defectivity Counts for Unexposed Bulk Areas

### Contact Angle of Resist after Topcoat Removal



Defectivity Counts for Exposed Areas